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FIRST NAMED INVENTOR

Masaki YAMAMOTO

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2882

INFORMATION DISCLOSURE STATEMENT

(Use several sheets if necessary)

U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NO.	DATE	NAME	CLASS	SUB- CLASS	FILING DATE
	AA					

FOREIGN PATENT DOCUMENTS

DOCUMENT NO.	DATE	COUNTRY	TRANSLATION YES NO	ABSTRACT
AB				

OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, Etc.)

				TRANSLATION YES NO
CK	AC	M. Yamamoto, "Sub-nm FIGURE ERROR CORRECTION OF AN EUV MULTILAYER MIRROR BY ITS SURFACE MILLING", 7 th International Conference on Synchrotron Radiation Instrumentation, Book of Abstracts (August 21-25, 2000), pp.1-2.	X	
	AD	M. Yamamoto, "Sub-nm figure error correction of an extreme ultraviolet multilayer mirror by its surface milling", Nuclear Instruments and Methods in Physics Research A 467-468 (2001), pp. 1282-1285.	X	
	AE	M. Yamamoto and T. Namioka, "Layer-by-layer design method for soft-x-ray multilayers", Applied Optics, Vol. 31, No. 10, 1 April 1992, pp. 1622-1630.	X	
	AF	J. Braat, "Phase correcting layers in EUV imaging system for microlithography", Proceedings of the OSA TOPS on Extreme Ultraviolet Lithography, Optical Society of America (1996), pp.152-155.	X	
	AG	H. Kinoshita, et al., "Soft x-ray reduction lithography using multilayer mirrors", J. Vac. Sci. Technol. B 7 (6), Nov/Dec 1989, pp. 1648-1651.	X	
	AH	C. Gwyn et al., "Extreme ultraviolet lithography", J. Vac. Sci. Technol. B 16(6), Nov/Dec 1998, pp. 3142-3149.	X	
	AI	R. Stuik, et al., "Peak and integrated reflectivity, wavelength and gamma optimization of MO/Si, and Mo/Be multilayer, multielement optics for extreme ultraviolet lithography", J. Vac. Sci. Technol. B 17(6), Nov/Dec 1999, pp. 2998-3002.	X	
CK	AJ	P. H. Berning, "Physics of Thin Films", Advances in Research and Development, Volume 1 (1963), pp. 84-100.	X	

EXAMINER

/Chih-Cheng Kao/

DATE CONSIDERED

12/19/2006

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.